

Prototyping and Data Analysis of the 65 nm CMOS Sensor for High Energy Physics

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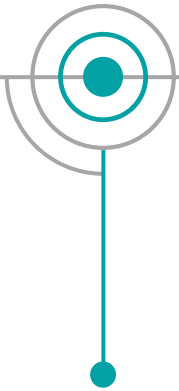
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June 22, 2023

OUTLINE



Introduction



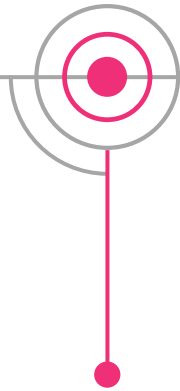
Tracking and Vertexing
Why silicon ?
ALICE-ITS upgrade

Evaluate the performance of
the CE65 sensor



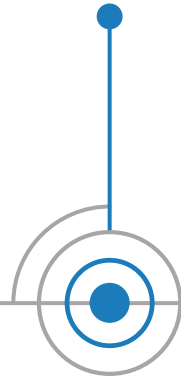
Objectives

Materials & Methods



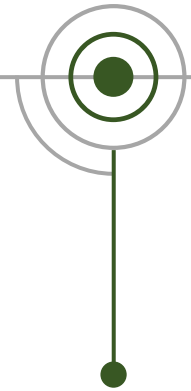
CE65 design and variants
Experimental setup
Analysis flow

Efficiency
Residual
Charge sharing
Cluster and Seed charge



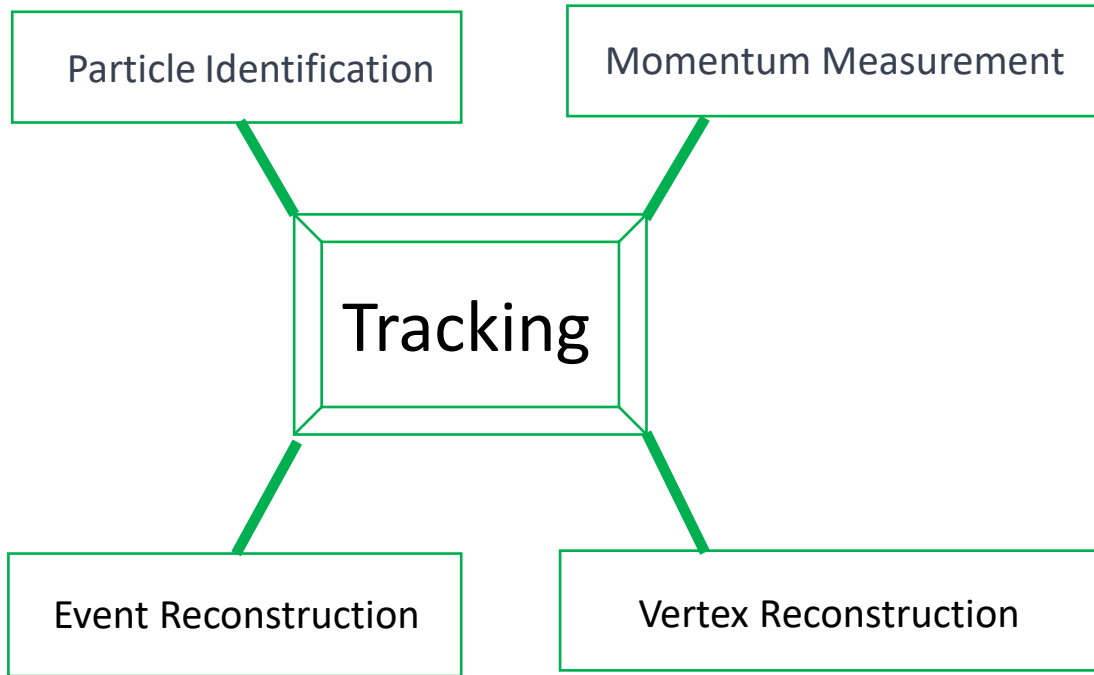
Results & Discussion

Conclusions



Conclusion
and
Future Work

Tracking and Vertexing



Vertex detector close to the interaction point

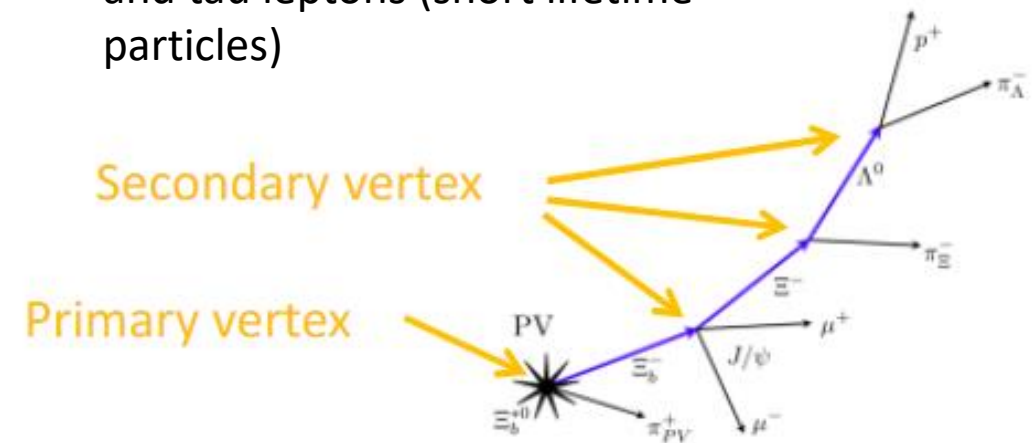


Reduce multiple scattering

Measurement of secondary vertices

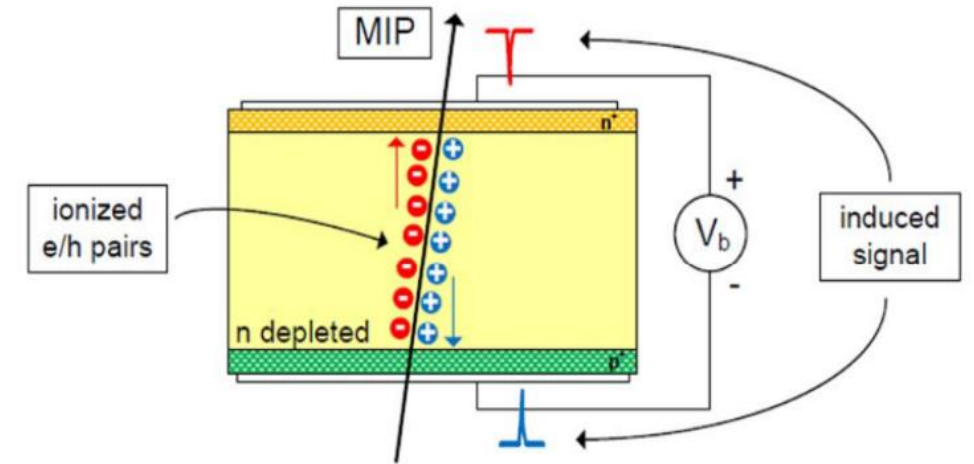


Identify heavy flavour particles and tau leptons (short lifetime particles)

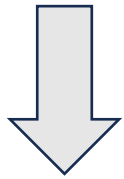


Why silicon ?

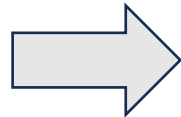
- **Low ionization energy:** 3.6 eV compared to 30 eV for gas detectors
- **High density:** 80 electron-hole pairs (MIP case)



Charged particles undergo ionization



Electrical charge carriers are separated by an electric field



collected on electrodes

Reverse bias is applied to a PN junction

Currents generated

Drift Current:

$$J_{\text{diffusion}} = -q \cdot D_{e/h} \cdot \frac{dn}{dx}$$

Diffusion Current:

$$J_{q_{n/p}} = q_{n/p} \cdot \mu(E) \cdot E$$

q: charge carrier
D: diffusion coefficient
n: number density of charge carriers
 μ : mobility
E: electric field

ALICE ITS upgrade

180 nm CMOS imaging technology

- 7 layers of MAPS
- Pixel size $27 \times 29 \mu\text{m}^2$
- Thickness $50 \mu\text{m}$
- **0.3 % X0 /inner layer**

CMOS sensor

combination of an active sensor and readout on a single silicon wafer

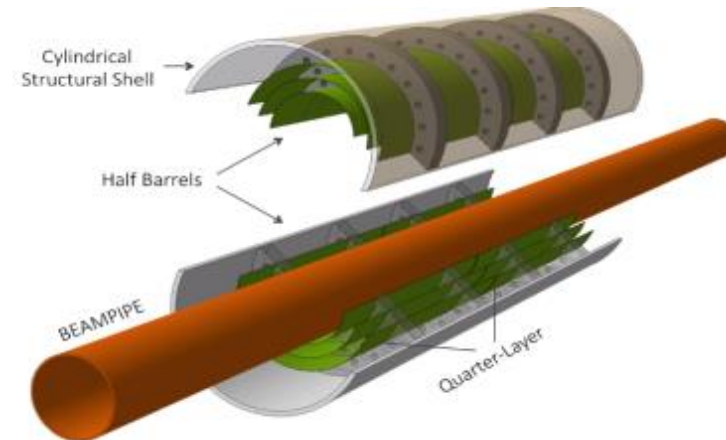
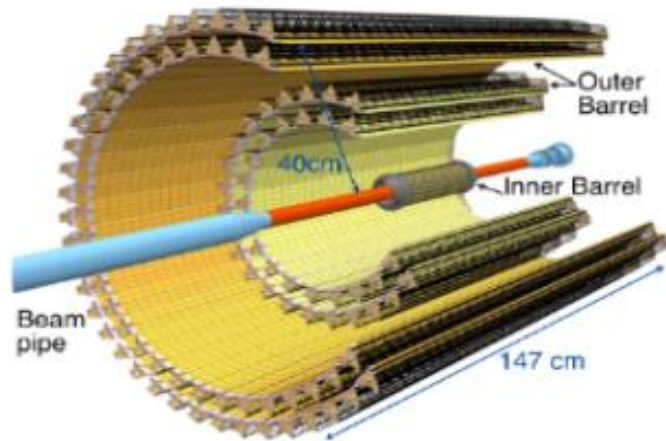


Reduce cost and scattering material

65 nm CMOS imaging technology

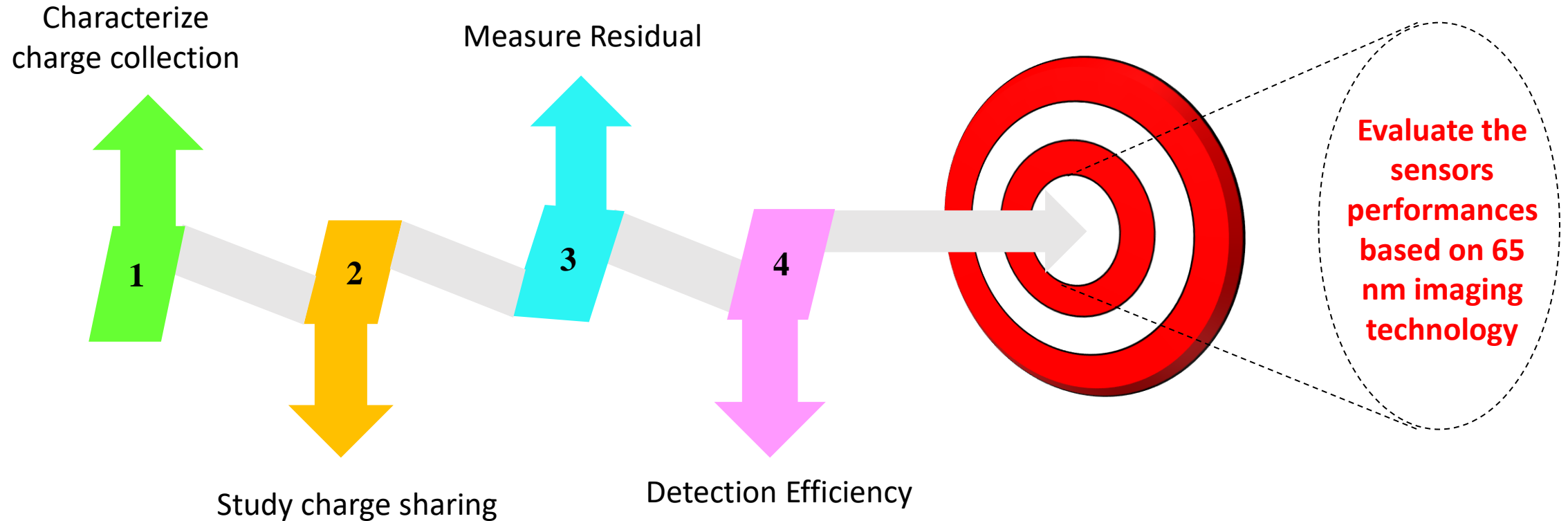
- 4 outer layers of ITS2
- 3 new fully cylindrical inner layers
- Pixel size $\sim 20 \times 20 \mu\text{m}^2$
- Thickness $30\text{-}40 \mu\text{m}$
- **0.05 % X0 /inner layer**
- **Bent sensors works well**

ITS2

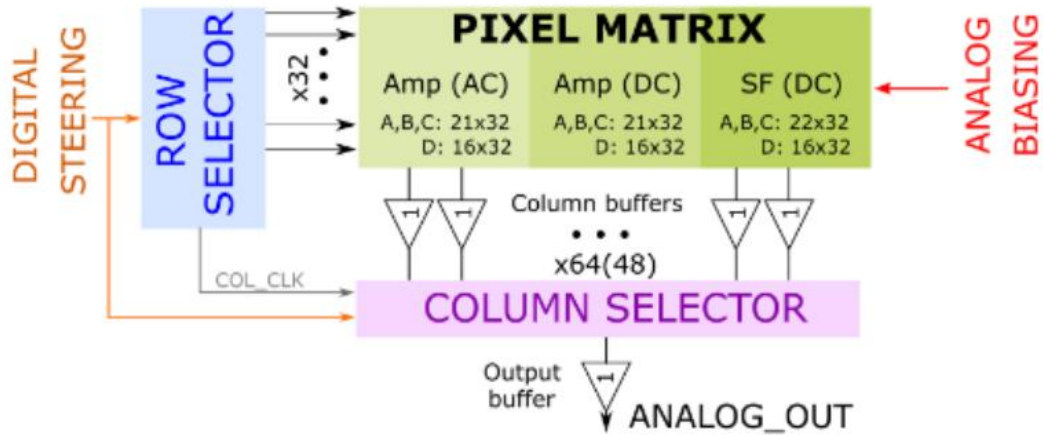


ITS3 Inner barrel

Objectives



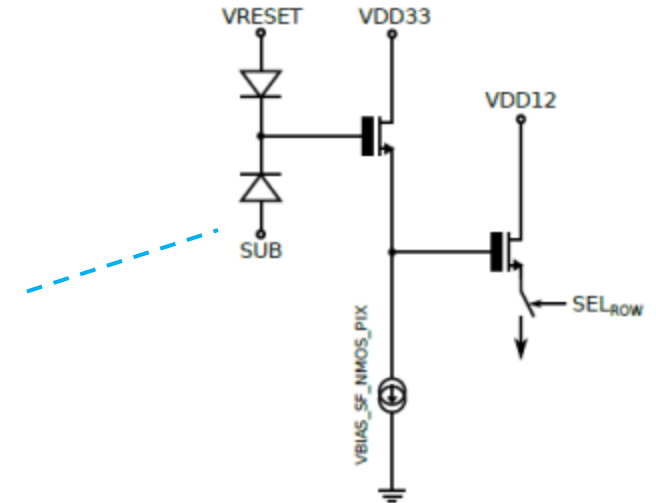
CE65 design



Thickness: 50 μm
 Rolling shutter readout
 Integration time: 200 μs (@10 MHz clock)
 Signal digitized outside the chip
Three sub-matrices:
AC coupled amplifier [Amp (AC)]
DC coupled amplifier [Amp (DC)]
SF source-follower [SF]

SF pixel

- Simplest approach
- Direct estimation of the input node voltage

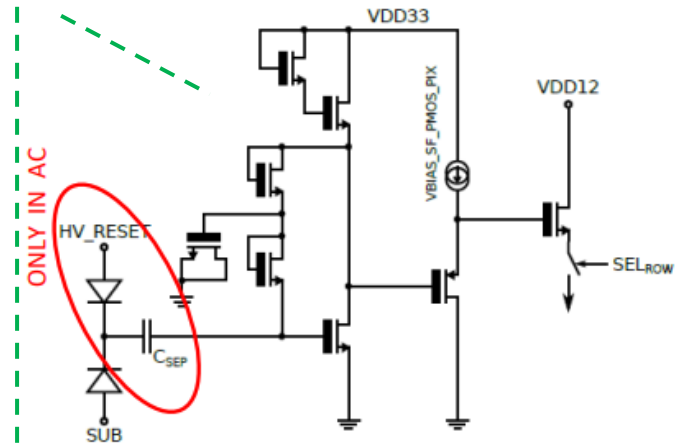


DC AMP

- Input voltage determined by the supply voltage
- Signal gain: 5 times

AC AMP

- Sensing node depletion voltage can be applied independently and go over the supply voltage
- Slightly reduced gain compared to DC



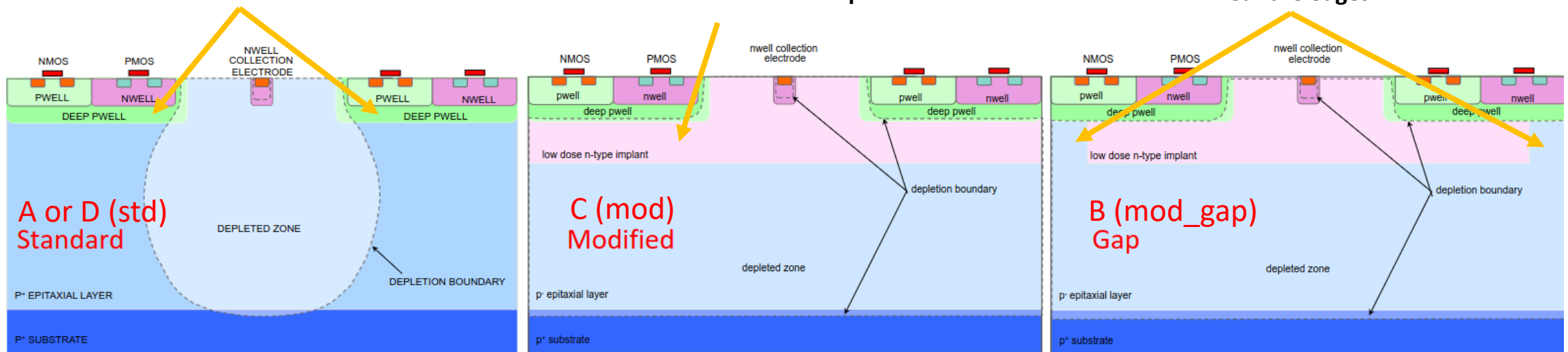
CE65 variants

Variant	Process	Pitch	Matrix	Sub-matrix
CE65-A	std	15 μ m	64 \times 32	AC/21, DC/21, SF/22
CE65-B	mod_gap	15 μ m	64 \times 32	AC/21, DC/21, SF/22
CE65-C	mod	15 μ m	64 \times 32	AC/21, DC/21, SF/22
CE65-D	std	25 μ m	48 \times 32	AC/16, DC/16, SF/16

Prevent circuitry's nwells from collecting charge

To obtain a full depletion

To overcome the weak electric field near the edges



Experimental setup

Telescope:

Reference Arms : 4 ALPIDE planes for track reconstruction

DUT : CE65

TRG : DPTS

Test beam:

May 2022 at CERN-PS

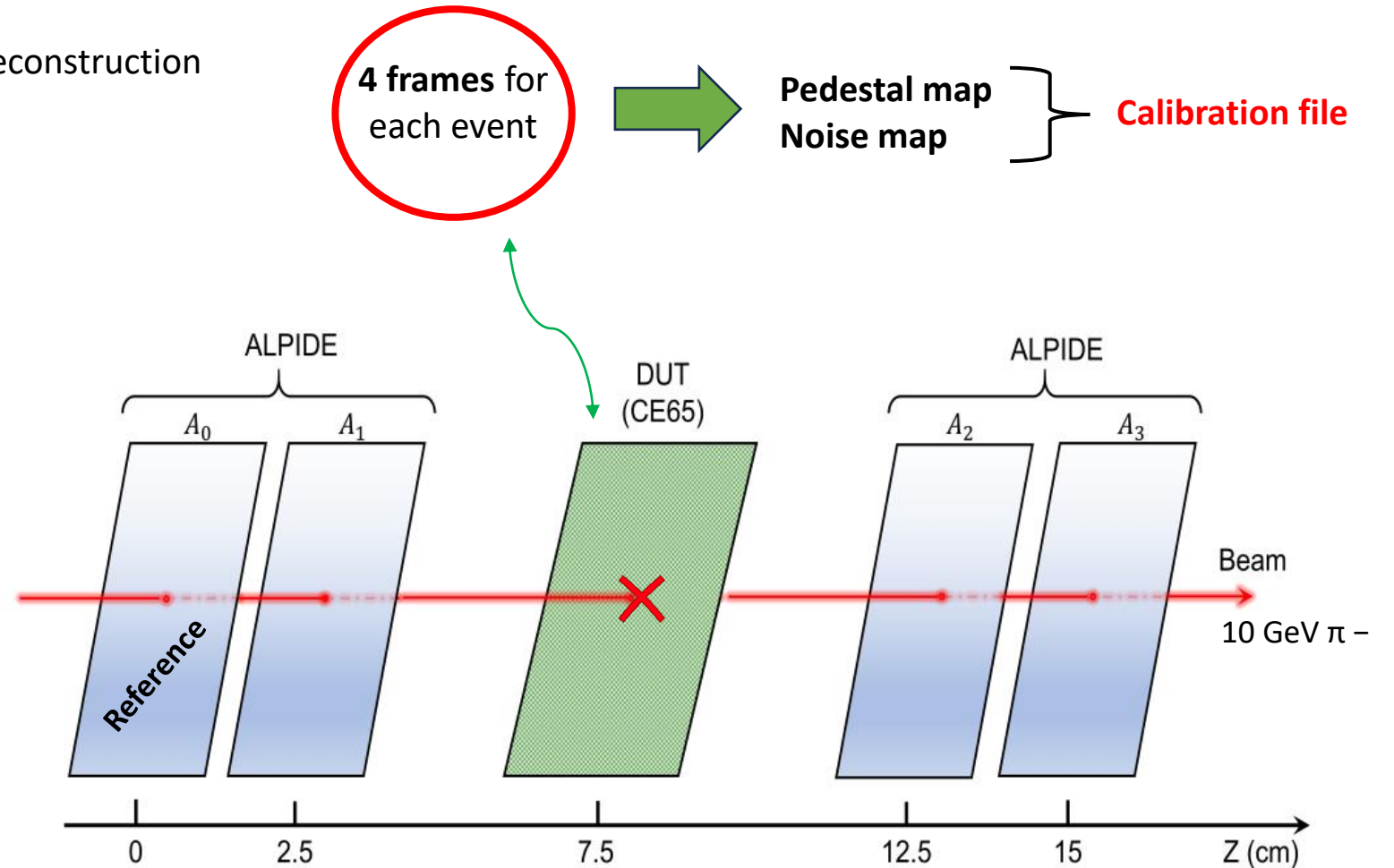
Data acquisition:

EUDAQ2

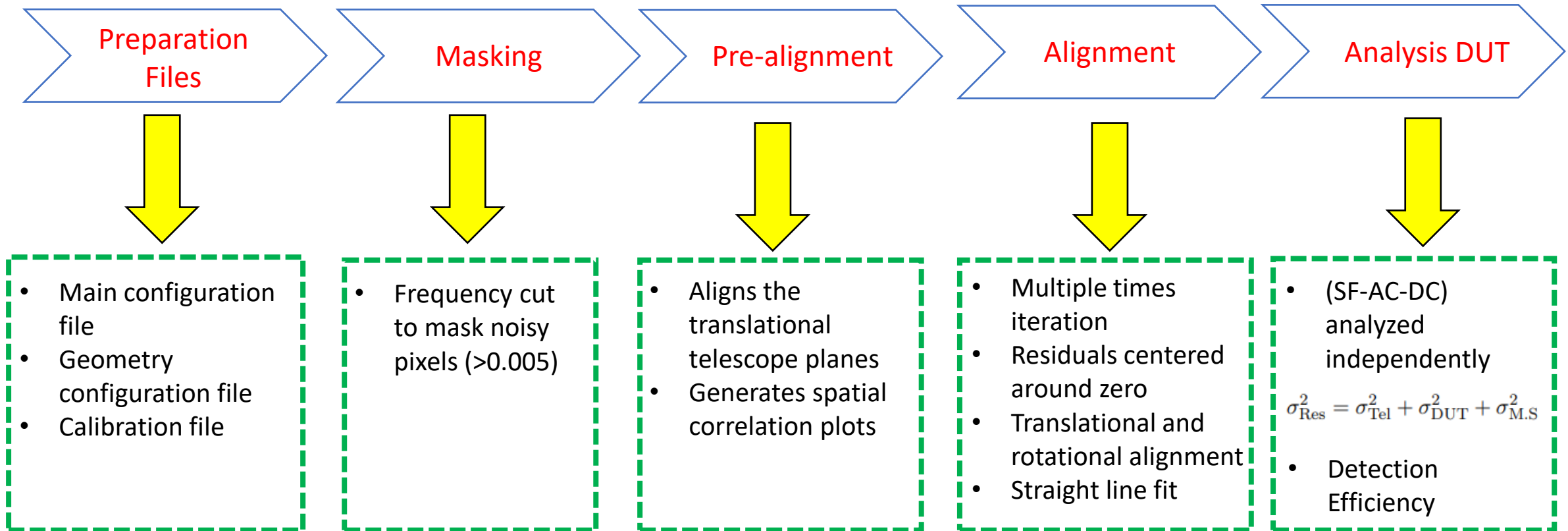
Event reconstruction algorithm
and data analysis framework:

Corryvreckan

Noise run-Beam run:
correlated double sampling
method (**CDS**)



Analysis flow



Reconstruction chain

Main Configuration file

Tracking: spatial cut at 100 μm , 100 μm for reference, 50 μm , 50 μm and $\chi^2/ndf < 1$ for DUT association

Clustering: Set 2 Thresholds and calculate position by center of gravity for 3x3 window

SF: seeding charge > 150 ADCu, SNR > 3

AC/DC: seeding charge > 500 ADCu, SNR > 3

Edge: drop track with interception at **2 pixels** to DUT edge.

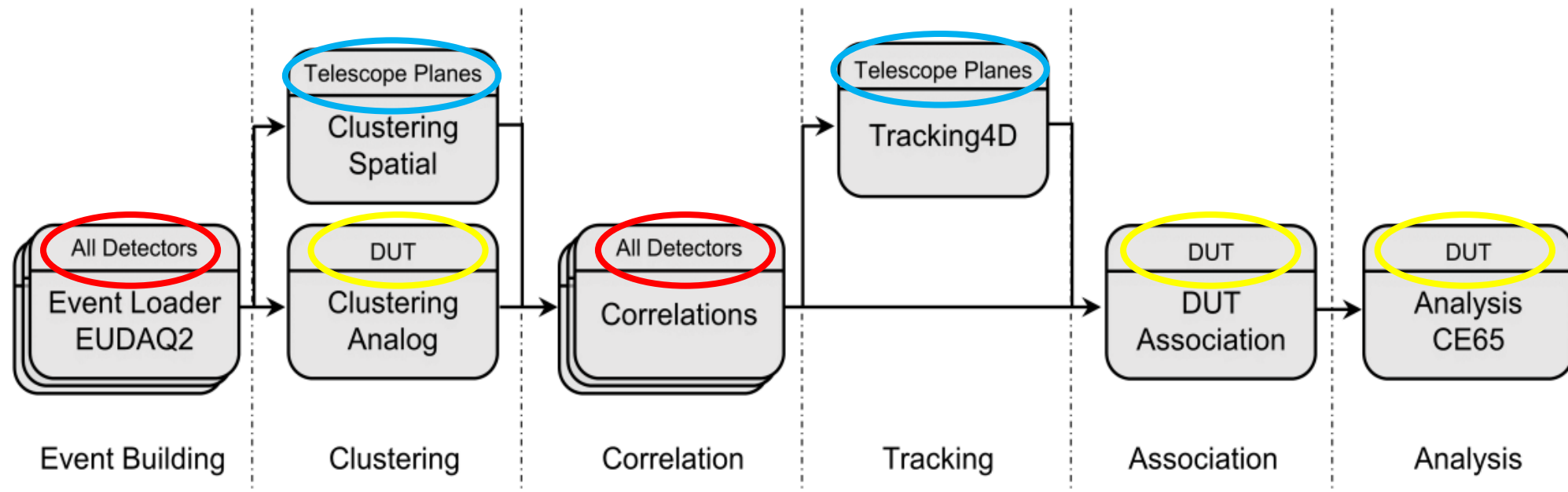
Seeding method: **multi** (probability of having more than one cluster per track)

Geometry file

position, number of pixels, spatial and time resolution for each detector

Region of interest

Calibration file



Cluster charge



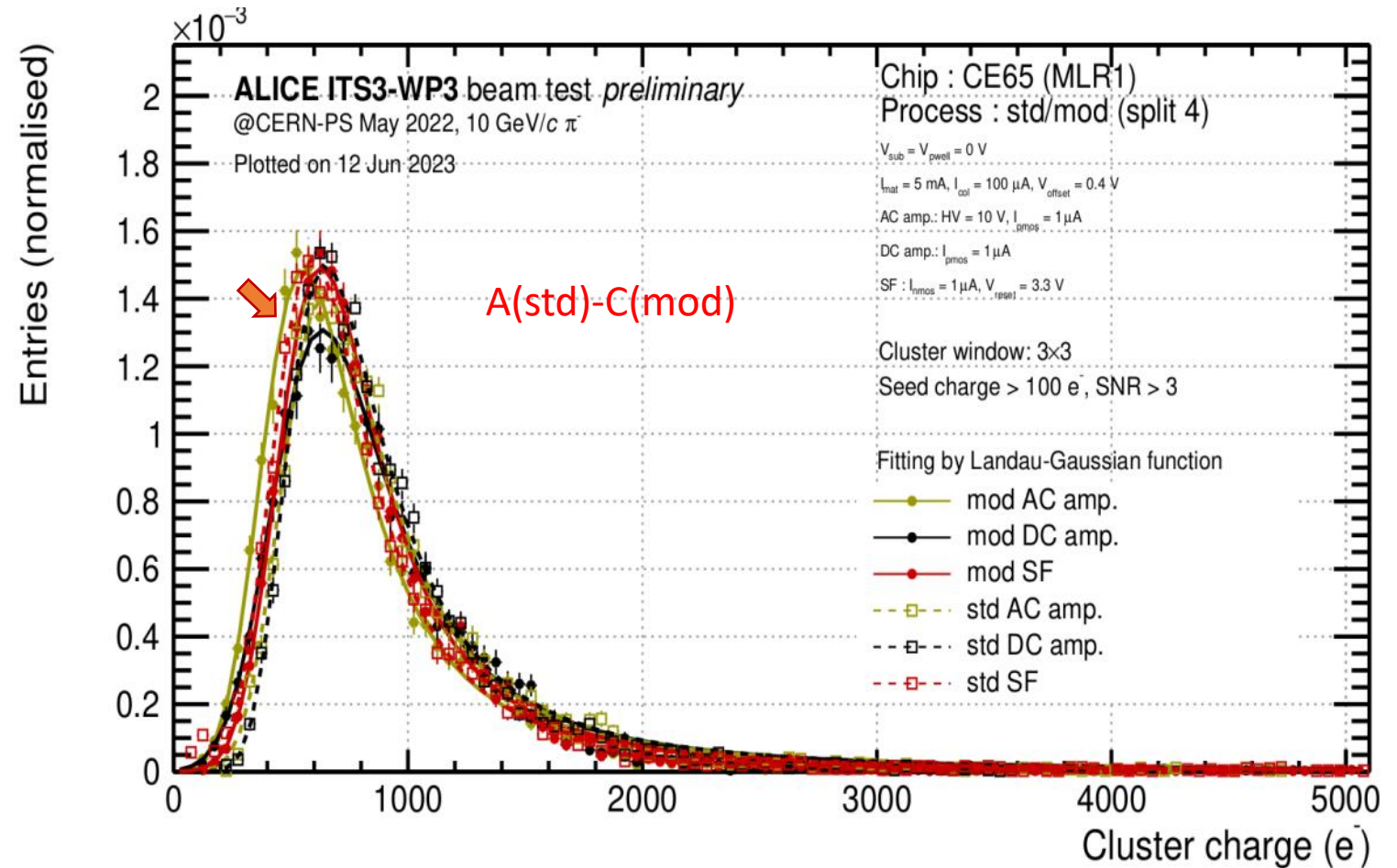
Expected: cluster charge is almost the same



Landau distribution
MPV range 550-600 electron

5	54	17
15	100	80
3	54	7

Seed charge



Seed charge



Expected : **C(mod)** a little bit closer to the **MPV**



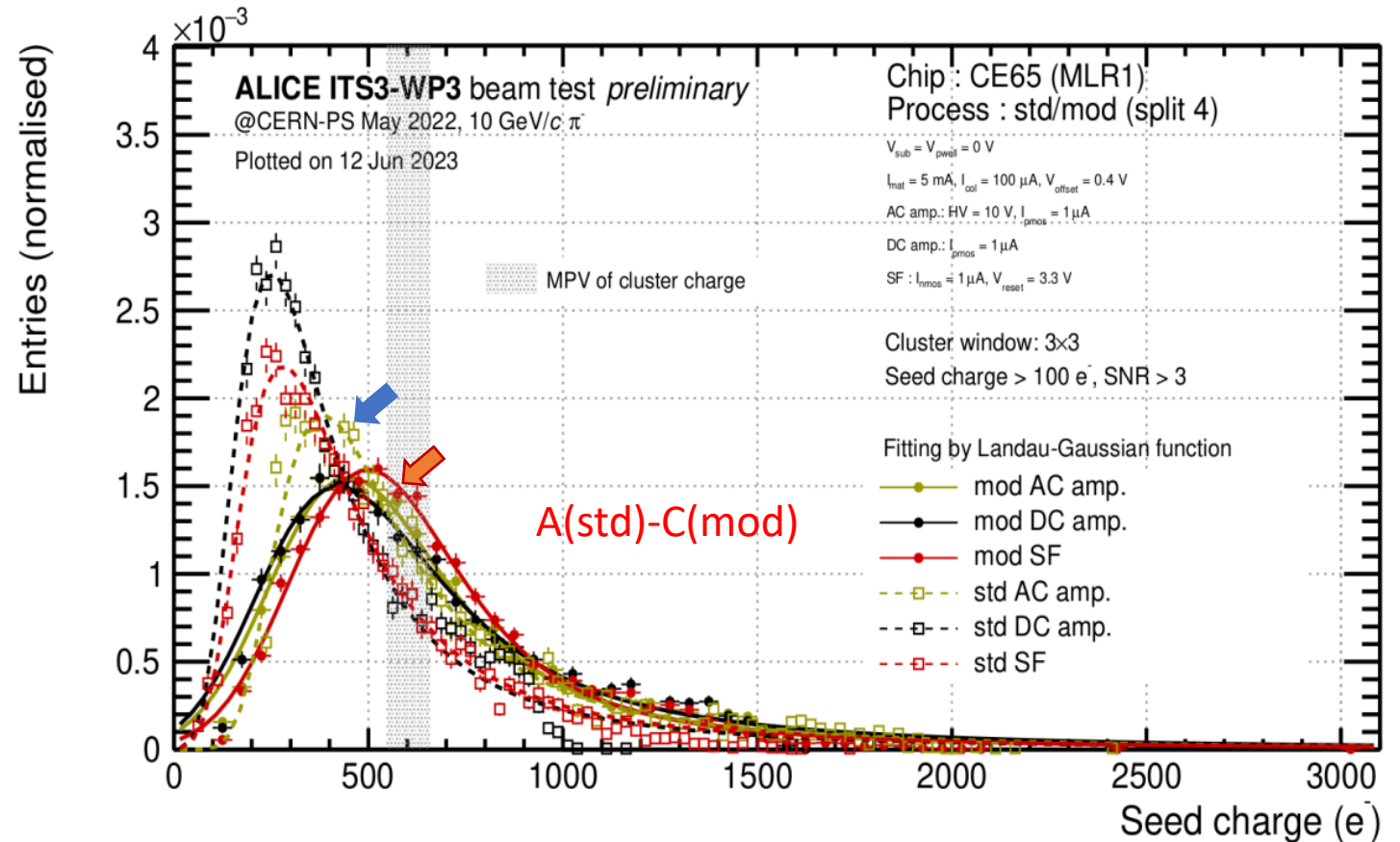
Less charge sharing than A(std)



Unexpected : **SF** in **C(mod)** shifted more toward **MPV**



Different calibration factor

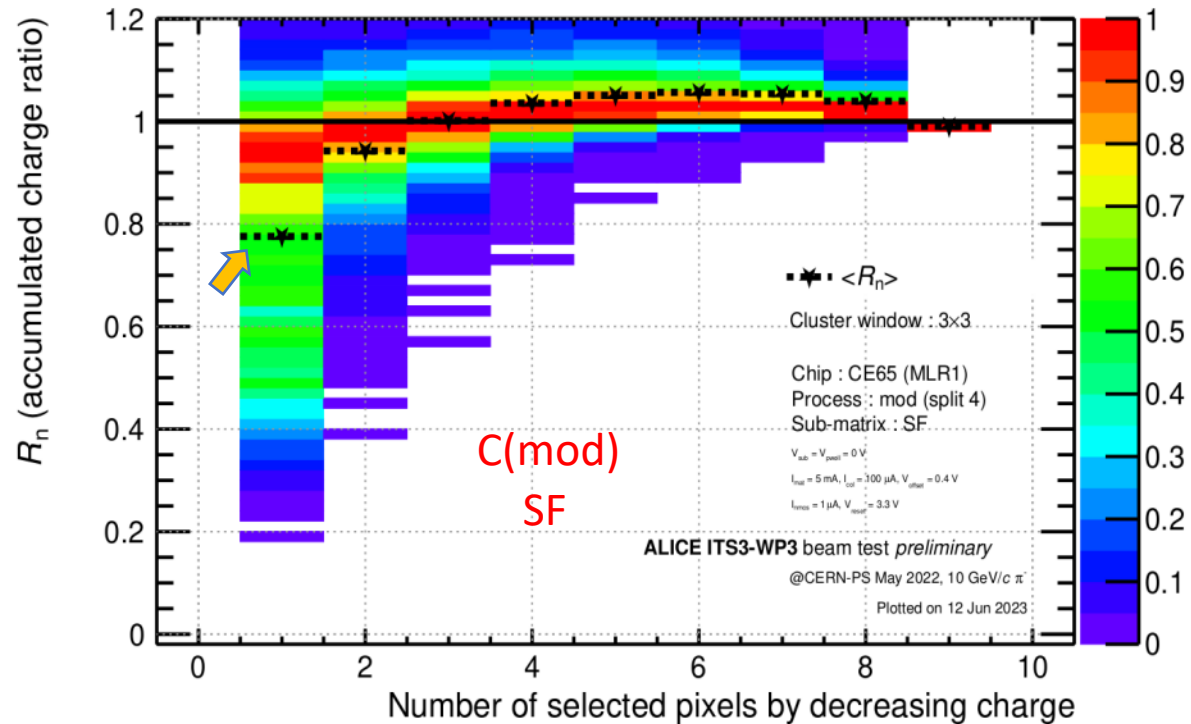


Charge sharing



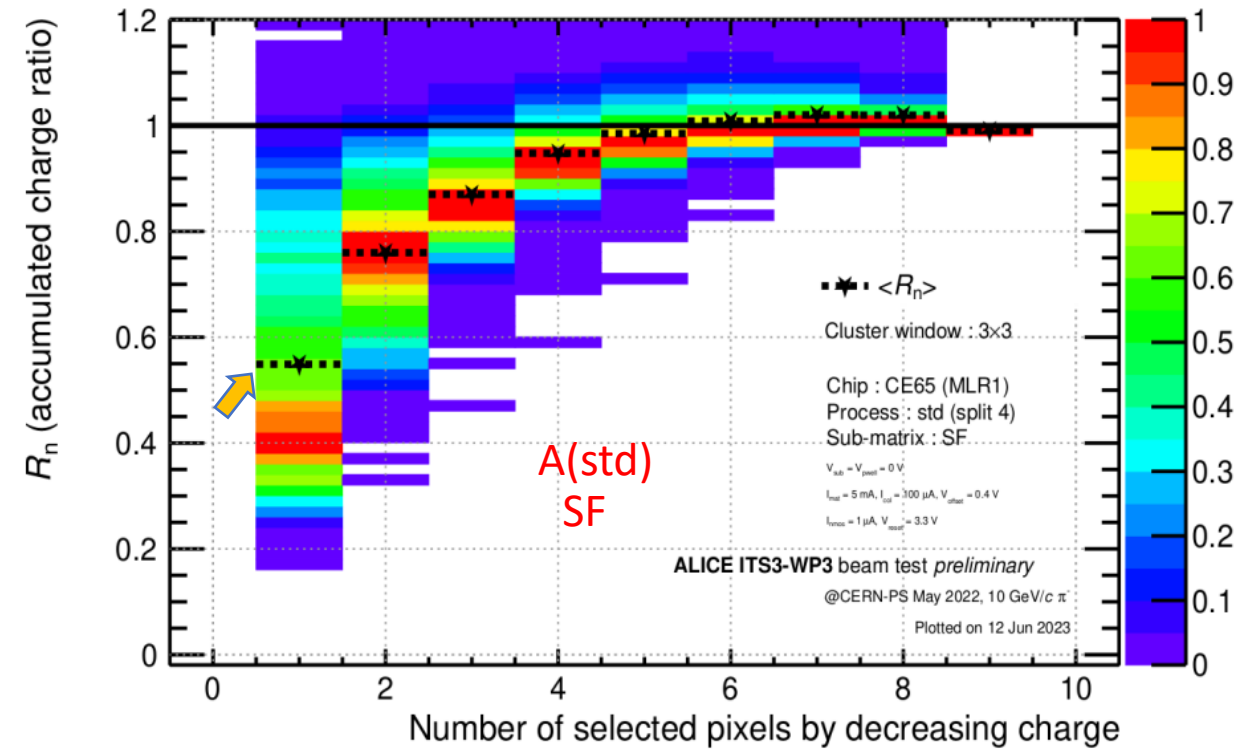
3 pixels contain all cluster charge

Seed pixel: contain around **80%** in average



6 pixels contain all cluster charge

Seed pixel: contain around **50%** in average



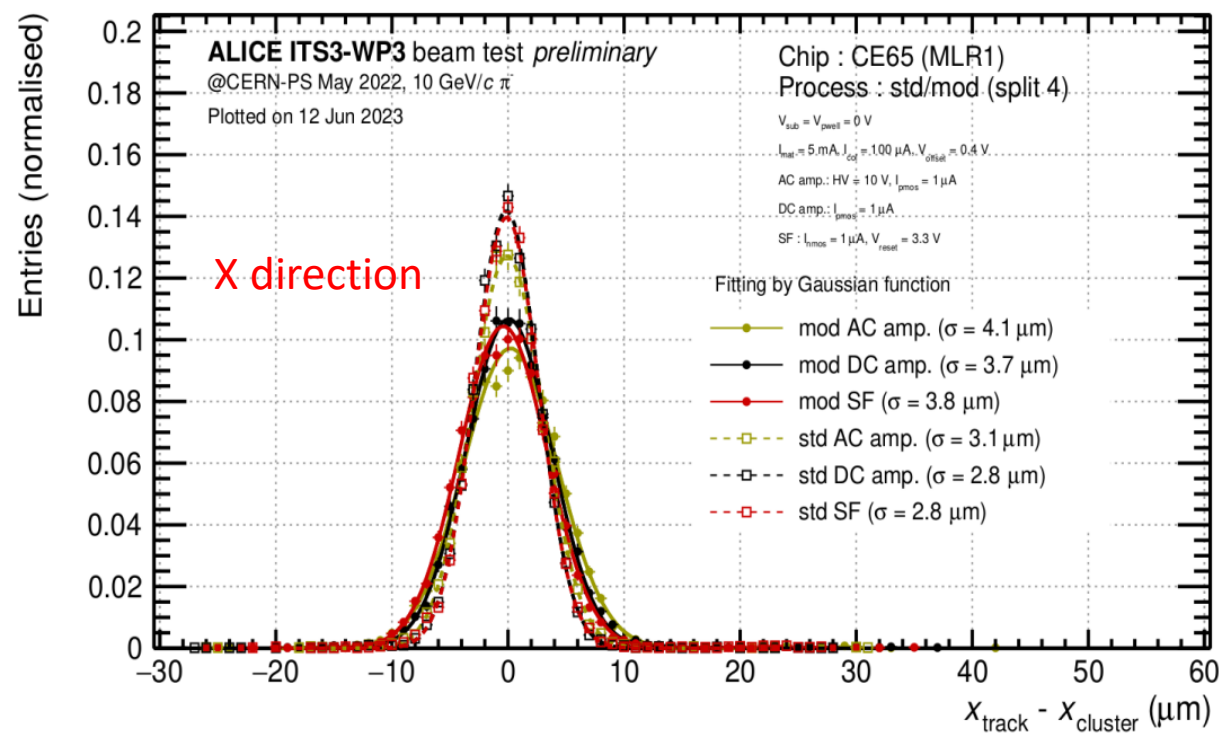
Residual



Better resolution for A(std)



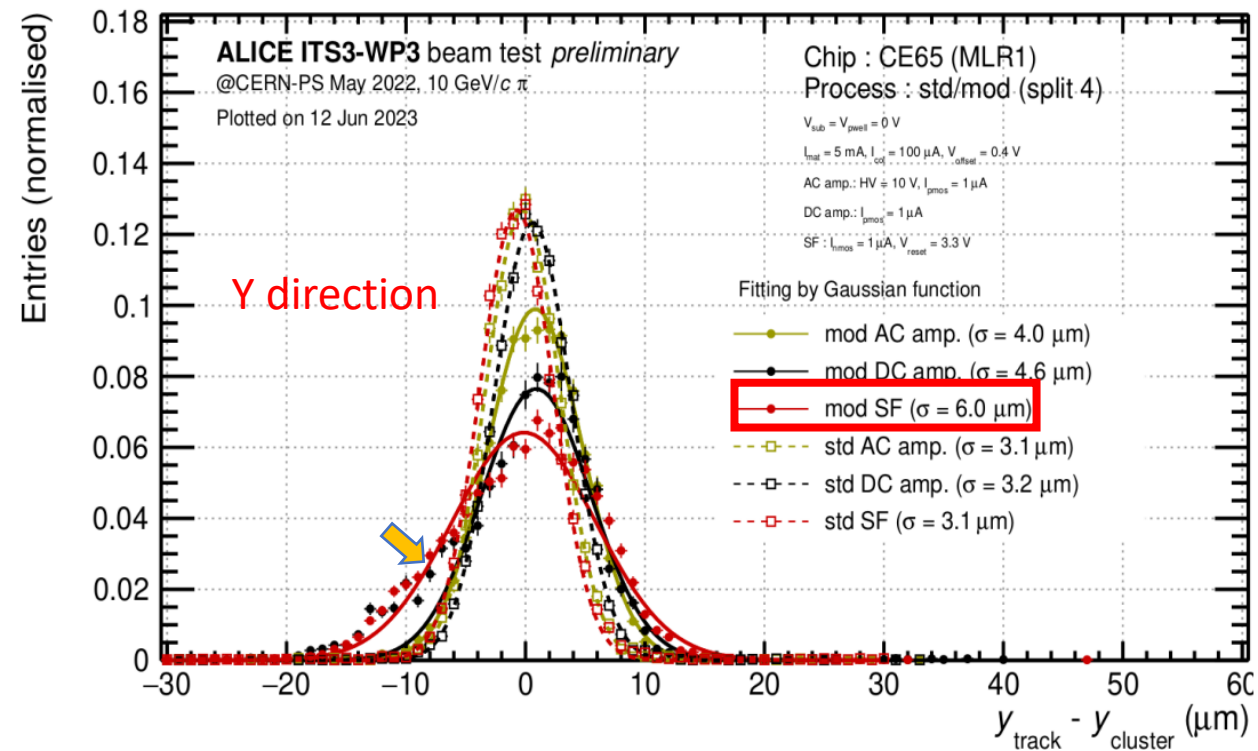
Less charge sharing affects the resolution



Poor resolution for SF in C(mod)



Bad alignment at Y



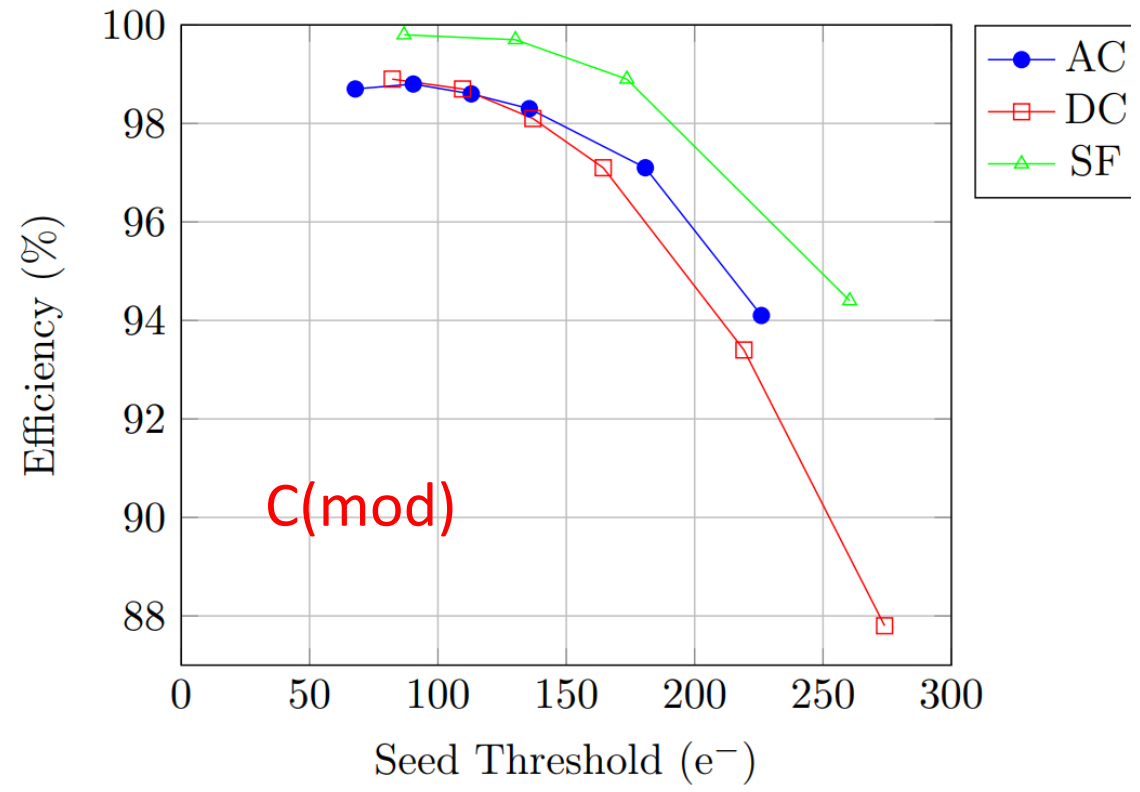
Efficiency



A(std) drop **faster** then that of chip C(mod)



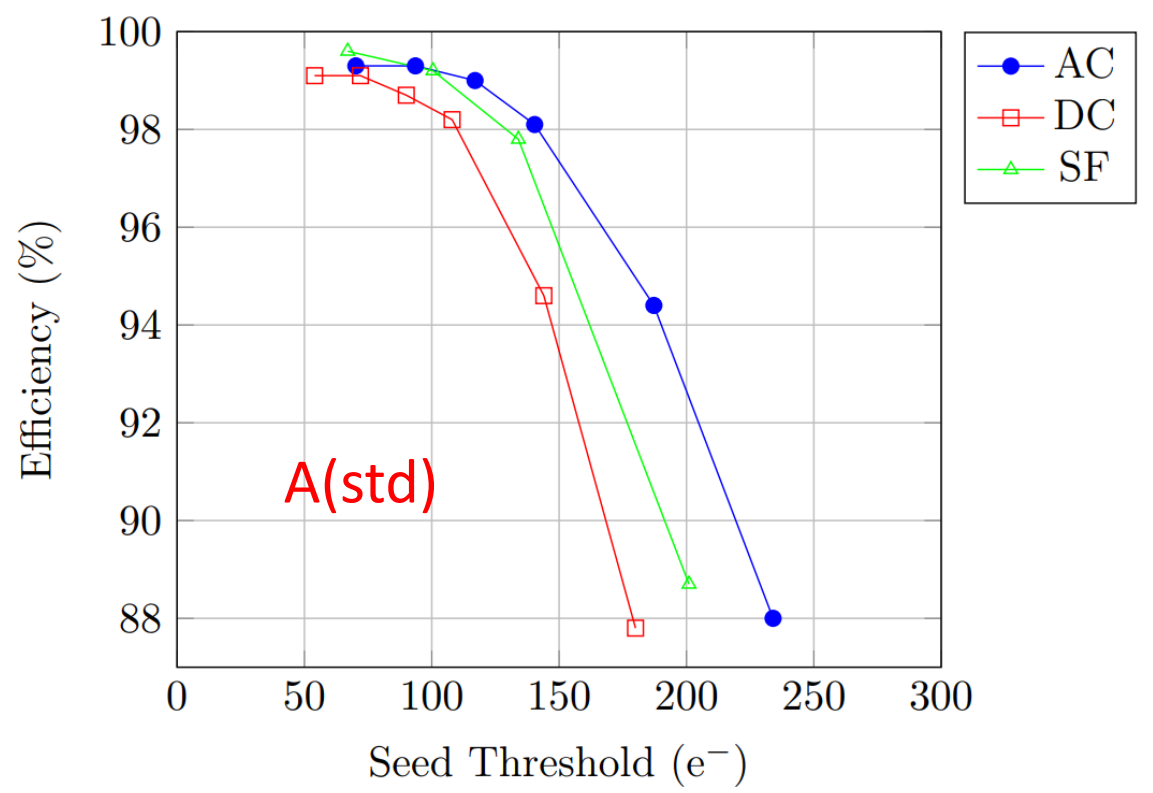
charge sharing **reduce** efficiency



AC in A(std) has the higher efficiency



Least charge sharing as observed in the shift toward MPV



Conclusions & Perspectives



Take Home Messages

- ✓ Cluster charge is not affected by the pixel doping process or the electronics architecture
- ✓ charge sharing reduce efficiency
- ✓ All cluster charge is mostly collected by a single pixel in the modified process



Future Work

1. Implementing η corrections to cluster positions. These corrections can help compensate for non-linear charge sharing effects
2. Analyze larger pixel sizes, like the D chip (25 μm)
3. Investigate more on the efficiency observed for C chip

Thank You For Your
Attention

